Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	276	RICHARDSON-JOHN	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:08
S2	36	RICHARDSON-JOHN-G	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:08
S3	2	RICHARDSON-JOHN-GILBERT	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:08
S4	21	S2 and conductiv\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:10
S5	1	S2 and conductiv\$5 and lump\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:09
S6	31	S1 and conductiv\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:10
S7	9	S1 and conductiv\$5 and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:12
S8	0	S1 and conductiv\$5 and (resistance\$1 or resistivit\$4) and lump\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:10
S9	806	bechtel.asn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:12

	1	· · · · · · · · · · · · · · · · · · ·		·		
S10	30	S9 and conductiv\$5 and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:12
S11	0	S9 and conductiv\$5 and (resistance\$1 or resistivit\$4) and lump\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:12
S12	0	("6889557").URPN.	USPAT	OR	OFF	2005/06/14 09:19
S13	38	("20030161946" "3596269" "3740522" "3742350" "4092950" "4340010" "4420251" "4472621" "4514443" "4529974" "4661682" "4677371" "4704985" "4736157" "4774905" "4853515" "4926165" "5015958" "5024423" "5181962" "5185183" "5195046" "5279148" "5369366" "5410255" "5412173" "5416280" "5551484" "5573814" "5602492" "5743299" "5951761" "6058978" "6085413" "6194890" "6197168" "6320400" "6501278").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:21
S14	1801	(lump\$3 with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:22
S15	588	(lump\$3 with (resistance\$1 or resistivit\$4)) and conductive	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:23
S16	198	(lump\$3 with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 10:45
S17	35	"4814690"	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:30
S18	2	S17 and conductive and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:31
S19	8	"5165794"	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:31

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S20	1	S19 and conductive and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:32
S21	10	"5381333"	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:32
S22	5	S21 and conductive and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:34
S23	12	"5911158"	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:34
S24	1	S23 and conductive and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:35
S25	2	"6088655"	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:35
S26	2	S25 and conductive and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:37
S27	2	"6501984"	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:37
S28	2	S27 and conductive and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:38
S29	1	"20030196485"	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:38
S30	0	S29 and conductive and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:38
S31	1141	((lump\$3 or net) with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 10:55
S32	14	((lump\$3 or net) with (resistance\$1 or resistivit\$4) with (model\$1 or modelling\$1)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 10:46
S33	712	((lump\$3 or net) with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 13:54

S34	12	((lump\$3 or net) with (resistance\$1 or resistivit\$4) with (model\$1 or modelling\$1)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:43
S35	329	(702/65).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:05
S36	556	(702/57).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:05
S37	305	(702/58).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:05
S38	619	(702/108).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:05
S39	312	(702/127).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:05
S40	66	(702/133).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:05
S41	3	S35 and ((lump\$3 or net) with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:06
S42	2	S36 and ((lump\$3 or net) with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:07
S43	1	S37 and ((lump\$3 or net) with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:44

Caa		C20 (/l +2	LIC DODIES	On	٥٢٢	2005/05/44 44 05
S44	0	S38 and ((lump\$3 or net) with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:06
S45	0	S39 and ((lump\$3 or net) with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:06
S46	353	(324/525).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:43
S47	157	(324/649).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:46
S48	364	(324/691).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:44
S49	392	(324/693).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:44
S50	344	(324/696).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:44
S51	1	S46 and ((lump\$3 or net) with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR ·	OFF	2005/06/14 11:46
S52	3	S47 and lump\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:46
S53	8	S47 and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:49

S54	78	S48 and conductive and	US-PGPUB;	OR	OFF	2005/06/14 11:50
	,,	((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	USPAT; EPO; JPO; DERWENT; IBM_TDB			2003/00/11 11:30
S55	115	S49 and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 12:14
S56	77	S50 and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:59
S57	379	((lump\$3 or net) near3 (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 13:58
S58	178	((lump\$3 or net) near3 (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4)) and resistivit\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 13:58
S59	52	((lump\$3 or net) near3 (resistance\$1 or resistivit\$4)) and (conductive with film\$1) and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4)) and resistivit\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 13:58

10828633_QUAL.txt

6172407 6408754 6475713 5386195 4505847 5764595 3794912 4313101 4393176 4446357 4566992 4774023 4849050 5937317 5968847 5989999 6011023 6346823 6346823 63452805 63452805 63452805 63452805 63452805 63452805 64452509 64468223 6475695 4632777 6157081 5602423 5736457 5602423 5736457 5977519 6084280 64964947 5015858 54964947 5015858 5181968 5196497 5015858 5181968 5196373	999382222222222222222222222222222222222
5730457 5977519 6084280 6200865 4450429 4492111 4573065 4593339 4794226 4904613 4960965 4964947 5015858 5181968 5196373	81 81 81 81 81 81 81 81 81

Page 1

10828633_CLS.txt Most Frequently Occurring Classifications of Patents Returned From A Search of 10828633 on June 14, 2005

```
Original Classifications
3 252/511
2 136/256
2 257/752
2 430/14
2 430/529
 Cross-Reference Classifications
                s-Reference (
430/531
430/536
257/E21.584
347/105
430/527
219/553
252/500
252/502
252/510
        3
3
        32222222222222
                 252/502
252/510
252/519.32
257/413
257/E21.165
257/E21.583
428/480
430/201
                 430/201
430/207
430/512
430/533
430/961
438/648
524/524
Combined Classifications
5 430/531
4 252/511
4 430/536
3 257/E21.584
        3332222222222222222222222
                  347/105
430/527
                 430/52/
136/256
219/553
252/500
252/502
252/510
252/519.32
257/410
                   257/412
                  257/413
257/752
257/E21.165
257/E21.583
                  428/480
430/14
                   430/201
                 430/201
430/207
430/512
430/529
430/533
430/961
438/627
                   438/648
```

2 524/495 2 524/524

10828633_CLSTITLES.txt Titles of Most Frequently Occurring Classifications of Patents Returned From A Search of 10828633 on June 14, 2005

```
(0 OR, 5 XR)
    430/531
                    430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
          class
                          COMPOSITION, OR PRODUCT THEREOF RADIATION SENSITIVE PRODUCT
           430/495.1
           430/523
                           .Identified backing or protective layer
                               containing
           430/531
                           ... Synthetic resin or cellulose derivative
                              containing
                   (3 OR, 1 XR)
252: COMPOSITIONS
    252/511
           Class
           252/500
                          ELECTRICALLY CONDUCTIVE OR EMISSIVE
                                 COMPOSITIONS
                           .Elemental carbon containing
           252/502
           252/510
                           ..With organic component
                           ...Resin, rubber, or derivative thereof
           252/511
                              containing
                     (0 \text{ OR}, 4 \text{ XR})
  4 430/536
                    430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
           Class
                             COMPOSITION, OR PRODUCT THEREOF
           430/495.1
                          RADIATION SENSITIVE PRODUCT
           430/523
                           .Identified backing or protective layer
                                containing
                           ..Synthetic rešin or cellulose derivative
           430/531
                               containing
                           ...Polymer of unsaturated monomer
           430/536
    257/E21.584
                     (0 \text{ or, } 3 \text{ xr})
                    257 : ACTIVÉ SOLID-STATE DEVICES
                         ...For electrical parameters, e.g., resistance, deep-levels, CV, diffusions by
           257/E21.531
electrical means
                                    (EPO)
                           .Manufacture or treatment of devices
           257/E21.532
                                  consisting of plurality of solid-state components
formed in
                                  or on common substrate or of parts thereof;
manufacture of
                                  integrated circuit devices or of parts thereof (EPO)
                           ..Manufacture of specific parts of devices
           257/E21.536
                                 (EPO)
           257/E21.575
                           ...Interconnections, comprising conductors and
                                dielectrics, for carrying current between separate
                                components within device (EPO)
                           ....Characterized by formation and post
           257/E21.576
                           treatment of dielectrics, e.g., planarizing (EPO)
.....Barrier, adhesion or liner layer (EPO)
           257/E21.584
                     (0 \text{ OR}, 3 \text{ XR})
    347/105
                    347 : INCREMENTAL PRINTING OF SYMBOLIC INFORMATION
           Class
           347/1
347/101
                           INK JET
                           .Medium and processing means
           347/105
                           ..Receiving medium
  3 430/527
                     (0 \text{ OR}, 3 \text{ XR})
                    430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
           Class
                             COMPOSITION, OR PRODUCT THEREOF
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10828633_CLSTITLES.txt
         430/495.1
                         RADIATION SENSITIVE PRODUCT
         430/523
                         .Identified backing or protective layer
                              containing
         430/527
                         .. Antistatic agent containing
                  (2 OR, 0 XR)
136 : BATTERIES: THERMOELECTRIC AND PHOTOELECTRIC
  136/256
         Class
         136/243
                         PHOTOELECTRIC
         136/252
                         .Cells
         136/256
                         .. Contact, coating, or surface geometry
   219/553
                   (0 \text{ OR}, 2 \text{ XR})
                  219 : ELECTRIC HEATING
         Class
         219/260
                         .Resistive element: igniter type
         219/538
                         .With heating unit structure
         219/552
                         ..Heating element structure
         219/553
                         ...Of particular construction and/or material
                            (e.g., infrared generator)
2 252/500
                  (0 OR, 2 XR)
252: COMPOSITIONS
         Class
         252/500
                         ELECTRICALLY CONDUCTIVE OR EMISSIVE
                            COMPOSITIONS
   252/502
                  (0 OR, 2 XR)
252: COMPOSITIONS
         Class
         252/500
                         ELECTRICALLY CONDUCTIVE OR EMISSIVE
                              COMPOSITIONS
         252/502
                         .Elemental carbon containing
   252/510
                   (0 OR, 2 XR)
                  252 : COMPOSITIONS
         252/500
                         ELECTRICALLY CONDUCTIVE OR EMISSIVE
                              COMPOSITIONS
         252/502
252/510
                         .Elemental carbon containing
                         ..With organic component
  252/519.32
                   (0 OR, 2 XR)
         Class
                  252 : COMPOSITIONS
                         ELECTRICALLY CONDUCTIVE OR EMISSIVE
         252/500
                                COMPOSITIONS
                         .Metal compound containing
         252/518.1
         252/519.3
                         . With organic compound
                         ... The organic compound is a natural resin,
         252/519.32
                            protein, lignin, carbohydrate, or derivative thereof
                  (1 OR, 1 XR)
257 : ACTIVE SOLID-STATE DEVICES
2 257/410
         Class
                         ...Enhancement mode or with high resistivity channel (e.g., doping of 10 15 cm -3 or less)
.Having insulated electrode (e.g., MOSFET, MOS
         257/264
         257/288
                             diode)
         257/410
                         ... Gate insulator includes material (including
                            air or vacuum) other than SiO 2
                   (1 OR, 1 XR)
2 257/412
                  257 : ACTIVÉ SOLID-STATE DEVICES
         Class
                         ... Enhancement mode or with high resistivity
         257/264
                         channel (e.g., doping of 10 15 cm -3 or less)
.Having insulated electrode (e.g., MOSFET, MOS
         257/288
                             diode)
         257/412
                         .. Gate electrode of refractory material (e.g.,
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10828633_CLSTITLES.txt polysilicon or a silicide of a refractory or platinum group metal) (0 OR, 2 XR) 257 : ACTIVE SOLID-STATE DEVICES 2 257/413 Class ...Enhancement mode or with high resistivity channel (e.g., doping of 10 15 cm -3 or less) .Having insulated electrode (e.g., MOSFET, MOS 257/264 257/288 diode) 257/412 ..Gate electrode of refractory material (e.g., polysilicon or a silicide of a refractory or platinum group metal) ...Polysilicon laminated with silicide 257/413 (2 OR, 0 XR) 257 : ACTIVF 257/752 class ACTIVE SOLID-STATE DEVICES 257/734 COMBINED WITH ELECTRICAL CONTACT OR LEAD .Of specified material other than unalloyed 257/741 aluminum 257/750 257/752 ..Layered ...Planarized to top of insulating layer 257/E21.165 (0 OR, 2 XR)257 : ACTIVE SOLID-STATE DEVICES Class 257/E21.001 PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE OR TREATMENT OF SEMICONDUCTOR OR SOLID-STATE DEVICES OR OF PARTS THEREOF (EPO) .Manufacture or treatment of semiconductor device (EPO) 257/E21.002 ..Device having at least one potential-jump barrier or surface barrier, e.g., PN junction, 257/E21.04 depletion layer, carrier concentration layer (EPO) ...Device having semiconductor body comprising Group IV elements or Group III-V compounds with or 257/E21.085 without impurities, e.g., doping materials (EPO) 257/E21.158Manufacture of electrode on semiconductor body using process other than by epitaxial growth, diffusion of impurities, alloying of impurity materials, or radiation bombardment (EPO)Deposition of conductive or insulating 257/E21.159 material for electrode conducting electric current (EPO)From a gas or vapor, e.g., condensation 257/E21.16 (EPO)Of conductive layer (EPO) 257/E21.161On semiconductor body comprising Group 257/E21.162 IV element (EPO)Conductive layer comprising silicide 257/E21.165 (EPO) (0 OR, 2 XR) 257 : ACTIVE SOLID-STATE DEVICES 2 257/E21.583 ...For electrical parameters, e.g., resistance, deep-levels, CV, diffusions by 257/E21.531 electrical means

.Manufacture or treatment of devices

(EPO)

257/E21.532

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10828633_CLSTITLES.txt
                                       consisting of plurality of solid-state components
formed in
                                       or on common substrate or of parts thereof;
manufacture of
                                       integrated circuit devices or of parts thereof (EPO)
                               .. Manufacture of specific parts of devices
            257/E21.536
                                      (EPO)
            257/E21.575
                               ...Interconnections, comprising conductors and
                                     dielectrics, for carrying current between separate components within device (EPO)
            257/E21.576
                               ....Characterized by formation and post
                               treatment of dielectrics, e.g., planarizing (EPO) .....Planarization; smoothing (EPO)
            257/E21.583
                        (0 \text{ OR}, 2 \text{ XR})
     428/480
                       428 : STOCK MATERIAL OR MISCELLANEOUS ARTICLES
                              COMPOSITE (NONSTRUCTURAL LAMINATE)
             428/411.1
             428/480
                               .of polyester (e.g., alkyd, etc.)
     430/14
                        (2 OR, 0 XR)
                       430 :
                               RADIATION IMAGERY CHEMISTRY: PROCESS,
            Class
                                 COMPOSITION, OR PRODUCT THEREOF
             430/9
                              IMAGED PRODUCT
             430/14
                               .Multilayer
                        (0 OR, 2 XR)
     430/201
                                RADIATION IMAGERY CHEMISTRY: PROCESS,
             Class
                       430 :
                                 COMPOSITION, OR PRODUCT THEREOF
             430/199
                              TRANSFER PROCEDURE BETWEEN IMAGE AND IMAGE
                                     LAYER, IMAGE RECEIVING LAYERS, OR ELEMENT CONTAINING AN IMAGE RECEIVING LAYER OR AN INGREDIENT FOR FORMING AN
IMAGE
                                     RECEIVING LAYER
                               .Imagewise heating, element or image receiving layers therefor or imagewise vapor and gas transfer
             430/200
                                    process, element or image receiving layer therefor
                               ..Imagewise vapor or gas transfer process, element or image receiving layer therefor
             430/201
  2 430/207
                        (0 \text{ OR}, 2 \text{ XR})
                       430 :
                                RADIATION IMAGERY CHEMISTRY: PROCESS,
                                 COMPOSITION, OR PRODUCT THEREOF
             430/199
                              TRANSFER PROCEDURE BETWEEN IMAGE AND IMAGE
                                     LAYER, IMAGE RECEIVING LAYERS, OR ELEMENT CONTAINING AN IMAGE RECEIVING LAYER OR AN INGREDIENT FOR FORMING AN
IMAGE
                                     RECEIVING LAYER
             430/202
                               .Diffusion transfer process, element, or
                               identified image receiving layers therefor ... Element structurally defined other than
             430/207
                                  containing nominal processing composition container or
                                  trap, or containing processing composition container or trap made of identified material
                        (0 OR, 2 XR)
     430/512
                                RADIATION IMAGERY CHEMISTRY: PROCESS,
             Class
                       430 :
                              COMPOSITION, OR PRODUCT THEREOF
RADIATION SENSITIVE PRODUCT
.Antihalation or filter layer containing
..Filters ultraviolet radiation
             430/495.1
             430/510
             430/512
     430/529
                        (2 \text{ OR}, 0 \text{ XR})
             Class
                       430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
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10828633_CLSTITLES.txt
                              COMPOSITION, OR PRODUCT THEREOF
                            RADIATION SENSITIVE PRODUCT
           430/495.1
           430/523
                            .Identified backing or protective layer
                                  containing
                            .. Antistatic agent containing
           430/527
           430/529
                            ...Organic carboxylic, sulfur or phosphorus
                                acid or salt
  2
                      (0 \text{ OR}, 2 \text{ XR})
     430/533
                     430 :
           Class
                             RADIATION IMAGERY CHEMISTRY: PROCESS,
                              COMPOSITION, OR PRODUCT THEREOF
                            RADIATION SENSITIVE PRODUCT
           430/495.1
           430/523
                            .Identified backing or protective layer
                            containing
...Synthetic resin or cellulose derivative
           430/531
                                 containing
           430/533
                            ...Polyester or polycarbonate
     430/961
                      (0 \text{ OR}, 2 \text{ XR})
                     430 :
                             RADIATION IMAGERY CHEMISTRY: PROCESS,
           Class
                              COMPOSITION, OR PRODUCT THEREOF
           430/961
                            PROTECTIVE OR ANTIABRASION LAYER
  2
     438/627
                      (1 \text{ OR}, 1 \text{ XR})
                     438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
           Class
           438/584
                            COATING WITH ELECTRICALLY OR THERMALLY
                                      CONDUCTIVE MATERIAL
                            .To form ohmic contact to semiconductive
           438/597
                                    material
           438/618
                             ..Contacting multiple semiconductive regions
                                    (i.e., interconnects)
                            ...Multiple metal levels, separated by insulating layer (i.e., multiple level metallization) ....At least one metallization level formed of
           438/622
           438/625
                                 diverse conductive layers
                            ....At least one layer forms a diffusion barrier
           438/627
    438/648
                      (0 OR, 2 XR)
           Class
                     438 :
                            SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
           438/584
                            COATING WITH ELECTRICALLY OR THERMALLY
                                    CONDUCTIVE MATERIAL
           438/597
                            .To form ohmic contact to semiconductive
                                   material
                            ..Contacting multiple semiconductive regions
           438/618
                            (i.e., interconnects)
...Diverse conductors
           438/642
                            ....Having refractory group metal (i.e., titanium (Ti), zirconium (Zr), hafnium (Hf), vanadium
           438/648
(V)
                                niobium (Nb), tantalum (Ta), chromium (Cr), molybdenum
                                (Mo), tungsten (W), or alloy thereof)
    524/495
                      (1 \text{ OR}, 1 \text{ XR})
                     524 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
           Class
                            OF THE CLASS 520 SERIES
..Adding a NRM to a preformed solid polymer or preformed specified intermediate condensation product,
           524/1
                                 composition thereof; or process of treating or
composition
                                 thereof
```

	524/495	10828633_CLSTITLES.txtMixing with carbon, e.g., graphite, etc., having numerical limitations, other than amount, e.g., included herein are particle size, surface area, etc., or composition or product thereof, DNRM
2 524/	524	(0 OR, 2 XR)
	Class	524 : SYNTHETIC RESINS OR NATURAL RUBBERS PART OF THE CLASS 520 SERIES
	524/1	Adding a NRM to a preformed solid polymer or preformed specified intermediate condensation
product,		
• . •		composition thereof; or process of treating or
compositi	on	thereof
	524/500	Containing two or more solid polymers; solid polymers or SICP and a SICP, SPFI, or an ethylenic
reactant		
	524/502	or product thereofAt least one solid polymer derived from ethylenic reactants only
	524/515	Two or more solid polymers derived from ethylenic reactants only
	524/523	Solid polymer derived from carboxylic acid ester monomer
	524/524	Ester derived from an unsaturated alcohol and a saturated acid, e.g., vinyl acetate, etc.

above 1 abstract 1 ac 1 aces 1 acoustic 1 across 2 adapted 1 additionally 5 algebra 1 a113 along 4 already 1 an 6 analysis 4 analyze 1 analyzed 3 analyzing 2 and 27 anive 1 another 4 any 3 app 1 apparatus 4 applications 2 applied 3 are 9 area 4 around 5 art 1 as 8 at 15 attached 1 attorney 4 awarded 1 background 1 based 4 be 36 bearing 1 because 1 between 5 boundary 1 brwf 1 by 8 ce 2 certain 1 characteristics 5 characterization 1 characterize 1 characterizing 1 complex 1 comprising 1 concentration 1 concern 1 concerned 1 conducting 2 conductiv 1 conductive 23 configuration 1 configured 2 connect 1 contigured 1 contractual 1 controller 3

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needed 2
no 2
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nondestructive 1
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particular 2
pat 2
patent 1
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perfonn 1
periphery 5
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plurality 18
pnder 1
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present 5
previously 1
probe 11 probes 6
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procedures 1
processor 1
profile 2
profiled 1
programmed 1
prohibitive 1
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property 4
protile 1
radiographic 1
ray 1
related 1
relates 1
require 1
required 1
requires 1
requiring 2
resistance 14
resistive 1
resistivity 14
result 1
rights 1
same 1
sample 2
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sampler 1
samples 1
section 1
see 1
segments 1
select 1
selected 12
sent 1
signal 4
significant 1
small 1
solutions 2
somewhat 1
specific 1 specitic 1
states 3
stmcture 1
stnlcture 1
strain 10
stress 1
strtlcmres 1
strucmre 1
structure 22
structures 4
such 6
sud 2
sudace 1
suitably 1
sul 1
summary 1 support 1
sured 1
surement 1
surface 24
surfaces 1
surfacets 2
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techniques 5
techpiques 1
that 4
the 117
their 1
then 1
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thermal 2
thermographic 1
these 3
this 1
those 1
three 2
through 2
throughout 2
thus 1
tilm 7
time 1
to 33
tomography 3
two 2
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unfortunately 1
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use 1
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using 4
value 1
values 5
visualization 1
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volume 1
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where 2
wherein 1
which 4
while 1
which 4
while 1
wire 2
with 4
words 1
would 1
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